

Development of a Process Route to the FAK/ALK Dual Inhibitor TEV- 37440

Shawn P. Allwein^{†}, Dale R. Mowrey[†], Daniel E. Petrillo[†], James J. Reif[†], Vikram C. Purohit[†], Karen L. Milkiewicz[†], Roger P. Bakale[†], Michael A. Christie[†], Mark A. Olsen[§], Christopher J. Neville[§], and Gregory J. Gilmartin[§]*

[†]Chemical Process Research & Development, [§]Analytical Development, Teva Pharmaceuticals, 383 Phoenixville Pike, Malvern, PA 19355.

Supporting Information

¹H and ¹³C NMR spectra for all new chemical entities are included: S2-S15



























